ABSTRACT

The present invention provides a polishing composition for a magnetic disk substrate that can reduce scratches and surface roughness of a polished substrate without impairing the productivity, and a method for manufacturing a magnetic disk substrate using the polishing composition. The polishing composition for a magnetic disk substrate includes colloidal silica having a Δ CV value of 0 to 10% and water. The Δ CV value is a difference (Δ CV = CV30 − CV90) between a value (CV30) obtained by dividing a standard deviation based on a scattering intensity distribution at a detection angle of 30° according to a dynamic light scattering method by an average particle size based on the scattering intensity distribution and multiplying the result by 100 and a value (CV90) obtained by dividing a standard deviation based on a scattering intensity distribution at a detection angle of 90° according to the dynamic light scattering method by an average particle size based on the scattering intensity distribution and multiplying the result by 100.